

AMENDMENTS TO THE SPECIFICATION

Please replace the description of Figure 2 on page 11 of the specification with the following amended description:

Figure 2 shows a schematic of a microlithography projection exposure machine, including the catadioptric objective part of a projection objective with a physical beam splitter;

Please replace paragraph number 58, spanning pages 16 and 17, with the following amended paragraph:

The projection objective is designed for operating with a circularly polarized input light, and has between the object plane 26 and beam splitter 20 a $\lambda/4$ plate ~~47~~27 for converting the input light into a light that is s polarized with reference to the beam splitter surface 28. This plate 27 can consist, for example, of <110> oriented calcium fluoride. The light penetrates two lenses 24, 25 and is converted because of the retardation effect thereof, into circularly polarized light that is reflected by the concave mirror 21 and runs back through the retardation device 23. After renewed passage through the retardation lenses 24, 25, the light is p-polarized with reference to the beam splitter layer 28, and penetrates the latter without loss in the direction of a deflecting mirror 29 that deflects the light in the direction of the object plane. This explains, for example, that the $\lambda/4$ retarder, which is functionally necessary with such systems, between the beam deflection device 20 and concave mirror can be formed by one or more lenses with a suitable retardation effect. The $\lambda/4$ plate conventionally required between beam splitter and concave mirror can therefore be eliminated.